

1. A shadow mask in which throughholes are formed, each of said throughholes having a rear side hole portion through which an electron beam enters and a front side hole portion through which the electron beam is emitted so as to form a beam spot having a prescribed shape on a surface to be irradiated;

wherein, each of said throughholes has a ridge portion formed by intersection of a taper surface of said rear side hole portion and a taper surface of said front side hole portion;

the taper size T (= (S - Q)/2) represented by a value a half the difference between the hole width S at the end of said front side hole portion and the hole width Q at said ridge portion is within a range of from 30 to 40% of the thickness of said shadow mask; and

said ridge portion is formed at a sectional height of up to 35 μm from the end of said rear side hole portion.

2. A shadow mask according to claim 1, wherein the taper size T in the peripheral portion of said shadow mask is within a range of 30 to 40% of the thickness of said shadow mask.